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Dkong  
9/14/01

<b>Form PTO-1449 (modified)</b> List of Patents and Publications For Applicant's Information <del>Disclosure Statement</del> (Use several sheets if necessary)			ATTY. DKT. NO. 5298-02502	SERIAL NO. 09/779,123
			APPLICANT: Sethuraman et al.	GROUP: Unknown
			FILING DATE: February 7, 2001	2823

APR 27 2001

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>Lee</i>	B1	4,010,583	3/1977	Highberg	51	284	
<i>Lee</i>	B2	4,393,628	7/1983	Ottman et al.	51	281	
<i>Lee</i>	B3	5,294,570	3/1994	Fleming, Jr. et al.	438	800	
<i>Lee</i>	B4	5,602,423	2/1997	Jain	257	752	
<i>Lee</i>	B5	5,662,769	9/1997	Schonauer et al.	438	633	
<i>Lee</i>	B6	5,695,572	12/1997	Brunner et al.	134	3	
<i>Lee</i>	B7	5,782,675	7/1998	Southwick	451	56	
<i>Lee</i>	B8	5,786,260	7/1998	Jang et al.	438	401	
<i>Lee</i>	B9	5,919,082	7/1999	Walker et al.	451	41	
<i>Lee</i>	B10	5,963,841	10/1999	Karlsson et al.	438	952	
<i>Lee</i>	B11	5,972,124	10/1999	Sethuraman	134/438	691-7	
<i>Lee</i>	B12	5,972,792	10/1999	Hudson	438	691	
<i>Lee</i>	B13	6,010,964	1/2000	Glass	438	692	
<i>Lee</i>	B14	6,016,000	1/2000	Moslehi	257	522	
<i>Lee</i>	B15	6,042,996	3/2000	Lin et al.	430	313	
<i>Lee</i>	B16	4,193,226	3/1980	Gill, Jr. et al.	51	124R	
<i>Lee</i>	B17	4,811,522	3/1989	Gill, Jr.	51	131,1	
<i>Lee</i>	B18	5,421,769	6/1995	Schultz et al.	451	287	

**FOREIGN PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

<i>Lee</i>	B19	Malkoe et al., "Effect of Retaining Ring System on the Polishing of 300 mm Oxide-Wafers," March 2001, pp. 519-522.

EXAMINER:

*Keem May Lee*

DATE CONSIDERED:

*6/6/02*

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the patent owner.